

Witness Plate Testing

Goal of SEMATECH/Univ. Albany/IBM/AMD/Intel/IMEC effort:

Demonstrate high-outgas resist sample(s) that produce a high enough damage signal per wafer in TNO test to enable calibration of alternative witness plate test sites.

- § **Recall ASML/TNO fail if 2% reflectivity loss per 300mm wafer.**
- § **A sample that is near or above this level would validate ASML view on resist outgas test need for ADT tools.**
- § **A sample that is near or above this level will permit calibration of alternative test sites.**
 - **This would be very useful in extending study to HVM tools.**

Presentations:

Albany high-outgas sample development – Greg Denbeaux for Robert Brainard.

IBM high-outgas sample development – Greg Wallraff

